

PATENT ABSTRACTS OF JAPAN

(11)Publication number : **63-027448**
 (43)Date of publication of application : **05.02.1988**

(51)Int.CI.

**C07C 39/235
 C07C 37/66
 C07C 39/44
 C07C 43/23
 C07C 43/295
 C07C 45/61
 C07C 49/83
 C07C 49/84
 C07C147/10
 C07C148/00
 C07C149/36**

(21)Application number : **61-168590**(71)Applicant : **DAICEL CHEM IND LTD**(22)Date of filing : **17.07.1986**(72)Inventor : **ISHIKURA MOTOYUKI
 OKITSU KIYOSHI**

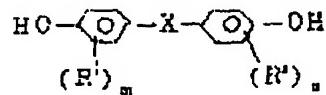
(54) PRODUCTION OF HIGH-PURITY DI-ALKALI METALLIC SALT OF BISPHENOL

(57)Abstract:

PURPOSE: To obtain an anhydrous uniform solution of the titled high-purity compound having an extremely low content of mono-alkali metallic salt substantially in an anhydrous state, by reacting a specific amount of a bisphenol alkali metallic salt-forming agent with a specific bisphenol.

CONSTITUTION: A bisphenol shown by formula (X is SO₂, CO, O, S, 1W6C alkylene and alkylidene, 5W15C cycloalkylene and cycloalkylidene; R₁ and R₂ are 1W3C alkyl and alkoxy, F, Cl or Br; m and n are 0W4) is reacted with 0.1W0.8 excess based on OH of the bisphenol of a bisphenol alkali metallic salt-forming agent such as KOH in an inert organic polar solvent so that the amount of mono-alkali metallic salt of bisphenol is ≤0.2mol and water in the system is removed to give the aimed compound useful as a raw material for polycondensation polymer, etc.

EFFECT: Is especially useful for raising molecular weight of polystyrene.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the

examiner's decision of rejection or application
converted registration]
[Date of final disposal for application]
[Patent number]
[Date of registration]
[Number of appeal against examiner's decision of rejection]
[Date of requesting appeal against examiner's decision of rejection]
[Date of extinction of right]

Copyright (C); 1998,2000 Japan Patent Office